(19) World Intellectual Property Organization

International Bureau





(43) International Publication Date 14 July 2005 (14.07.2005)

PCT

(10) International Publication Number WO 2005/064682 A1

(51) International Patent Classification7:

H01L 27/148

A## 40

(21) International Application Number:

PCT/US2003/039026

- (22) International Filing Date: 8 December 2003 (08.12.2003)
- (25) Filing Language:

English

(26) Publication Language:

English

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- (81) Designated States (national): AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BY, BZ, CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, ES, FI, GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NI, NO, NZ, OM, PG, PH, PL, PT, RO, RU, SC, SD, SE, SG, SK, SL, SY, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, YU, ZA, ZM, ZW.
- (84) Designated States (regional): ARIPO patent (BW, GH, GM, KE, LS, MW, MZ, SD, SL, SZ, TZ, UG, ZM, ZW), Eurasian patent (AM, AZ, BY, KG, KZ, MD, RU, TJ, TM), European patent (AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HU, IE, IT, LU, MC, NL, PT, RO, SE, SI, SK, TR), OAPI patent (BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG).

Declaration under Rule 4.17:

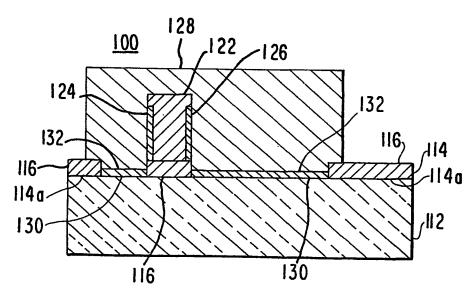
of inventorship (Rule 4.17(iv)) for US only

Published:

with international search report

For two-letter codes and other abbreviations, refer to the "Guidance Notes on Codes and Abbreviations" appearing at the beginning of each regular issue of the PCT Gazette.

(54) Title: SEMICONDUCTOR MEMORY DEVICE WITH INCREASED NODE CAPACITANCE



457) Abstract: An integrated circuit semiconductor memory device (100) has a first dielectric layer (116) characterized as the BOX is er absent from a portion (130) of the substrate (112) under the gate of a storage transistor to increase the gate-to-substrate capacitance and thereby reduce the soft error rate. A second dielectric layer (132) having a property different from the first dielectric layer is least partly covers that portion (130) of the substrate. The device may be a FinFET device including a fin (122) and a gate dielectric layer (124, 126) between the gate and the fin, with the second dielectric layer having less leakage than the gate dielectric layer.



